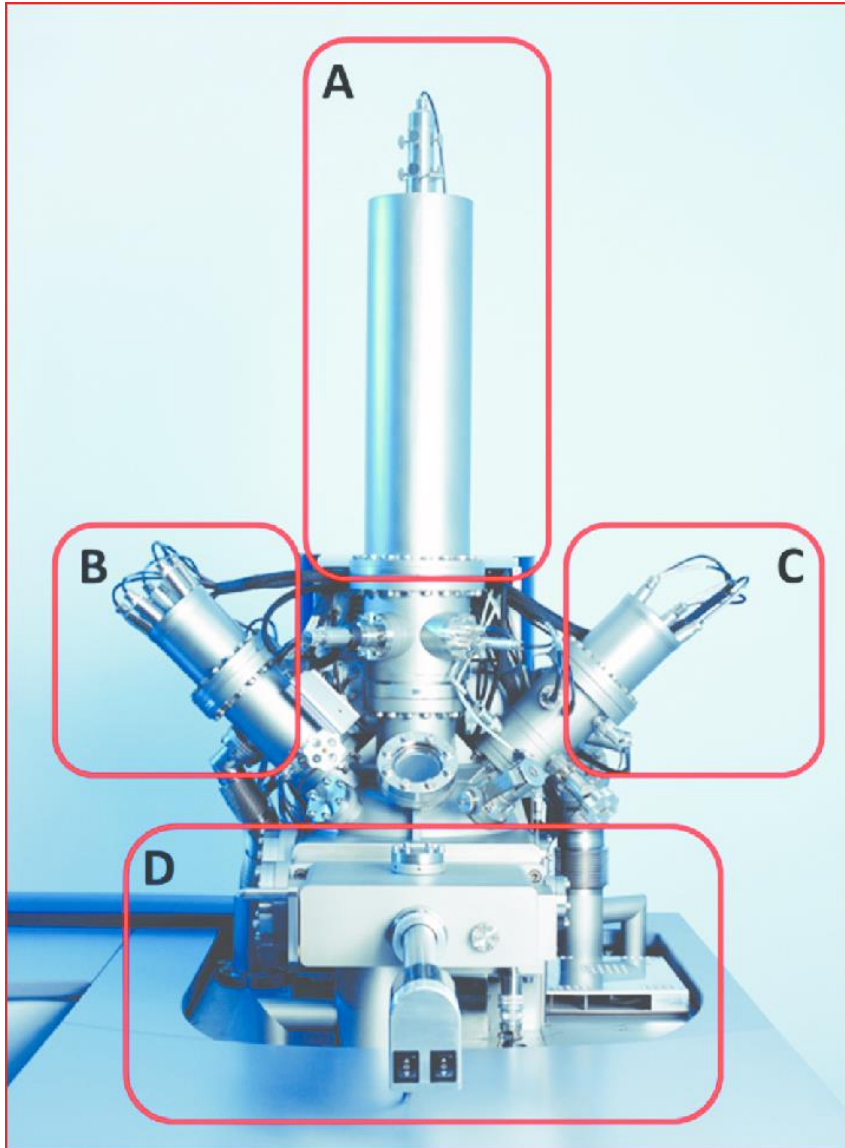


Time of Flight Secondary Ion Mass Spectrometry

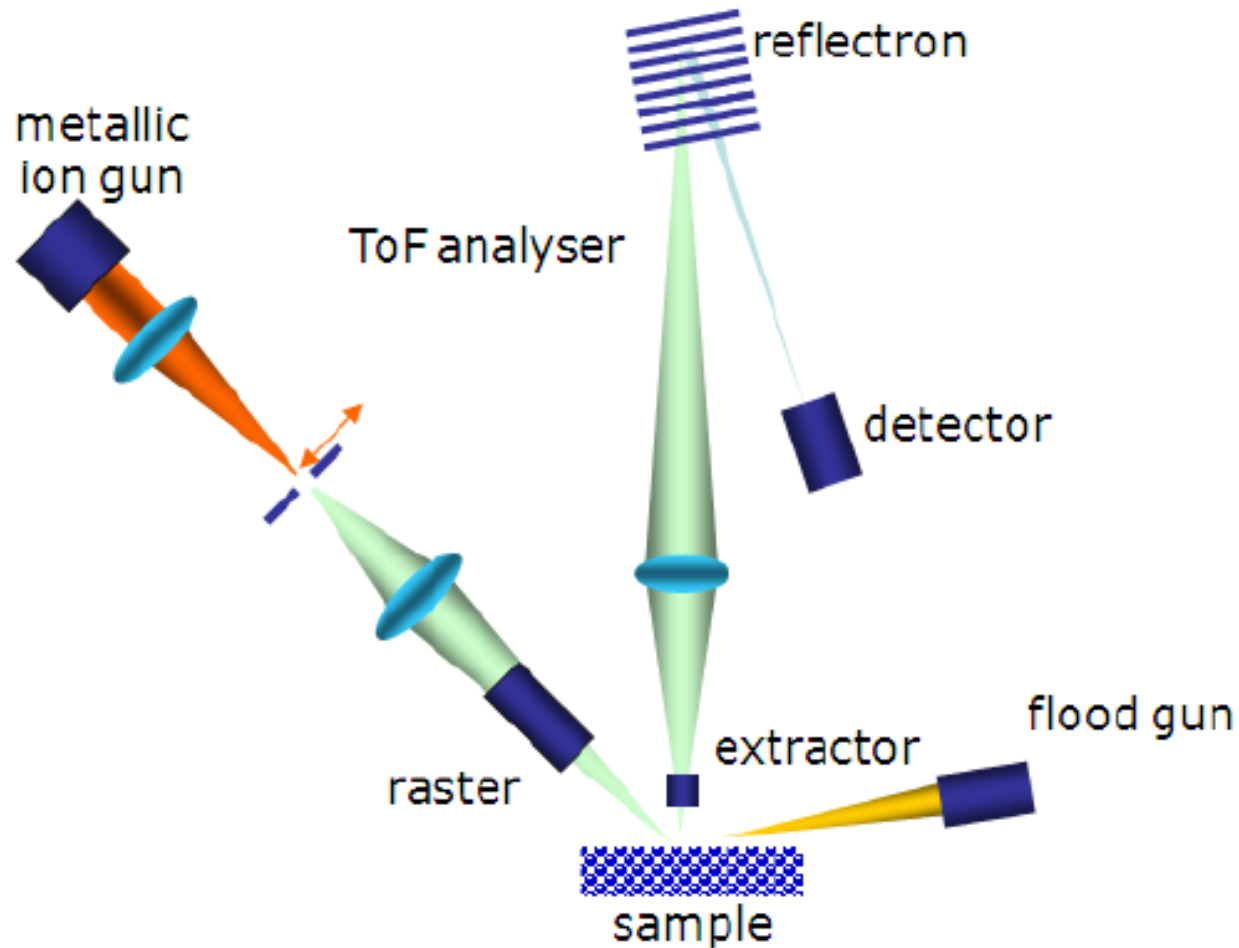
Somila & Nnamdi

Components



A- ToF analyser
B and C- Ion sources for sputtering and analysis
D- Load lock for sample introduction

Schematic Representation



Strengths and Limitations

- High sensitivity (ppm/ppb).
- Can detect all elements including Hydrogen
- Isotope sensitivity
- High mass range (up to 10000 amu)
- Short image acquisition time (minutes vs. hours for XPS)
- Limited quantification (requires standards)
- Destructive*

Modes of Operation

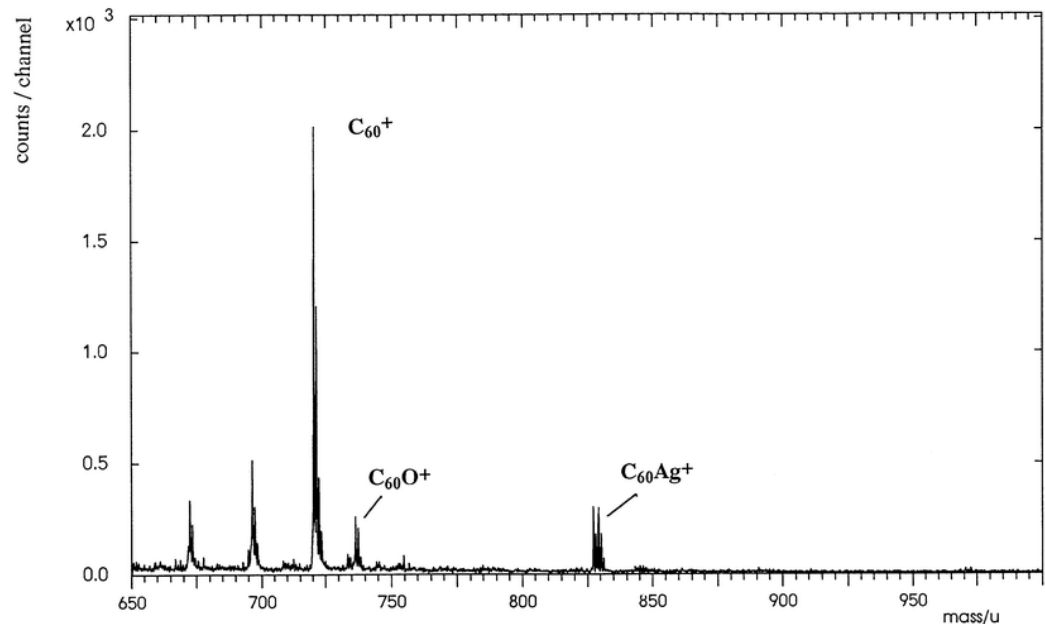
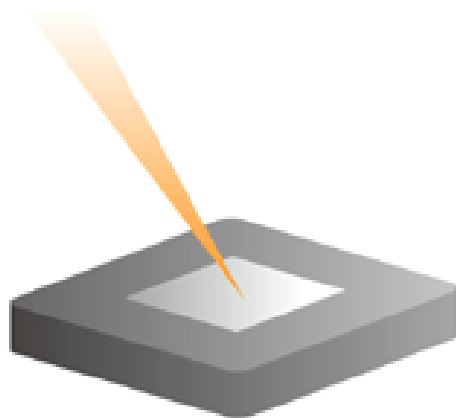
- **Surface Spectroscopy**
- **Surface Imaging**
- **Depth Profiling**
- **3D Analysis**

Surface Spectroscopy

A solid sample is bombarded with a pulsed primary ion beam. Atomic and molecular fragments are emitted from the outer layers of the sample and extracted. Measuring the “**time of flight**” for each ion allows the determination of its mass.

Surface Spectroscopy

Provides detailed mass spectral information about the outer monolayers of a surface.



Spectrum

Effects of primary beam on secondary ion yields

H																	He				
Li	Be															B	C	N	O	F	Ne
Na	Mg															Al	Si	P	S	Cl	Ar
K	Ca	Sc	Ti	V	Cr	Mn	Fe	Co	Ni	Cu	Zn	Ga	Ge	As	Se	Br	Kr				
Rb	Sr	Y	Zr	Nb	Mo	Tc	Ru	Rh	Pd	Ag	Cd	In	Sn	Sb	Te	I	Xe				
Cs	Ba	La	Hf	Ta	W	Re	Os	Ir	Pt	Au	Hg	Tl	Pb	Bi	Po	At	Rn				
Fr	Ra	Ac																			
Ce	Pr	Nd	Pm	Sm	Eu	Gd	Tb	Dy	Ho	Er	Tm	Yb	Lu								
Th	Pa	U	Np	Pu	Am	Cm	Bk	Cf	Es	Fm	Md	No	Lr								

O₂⁺ Primary

Positive Secondary

Cs⁺ Primary

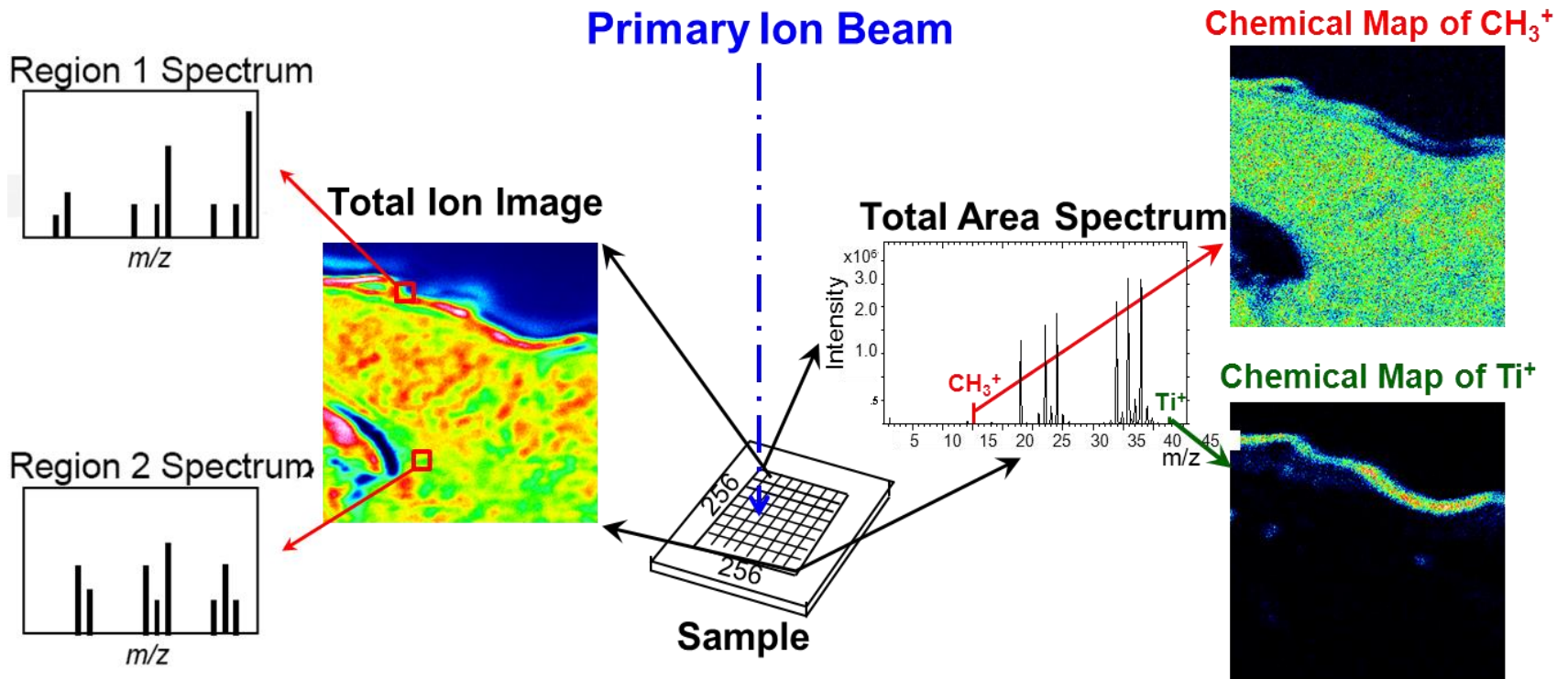
Negative Secondary

With an **oxygen beam**, the concentration of oxygen increases in the surface layer and metal-oxygen bonds are present in an oxygen-rich zone.

With a **cesium beam**, cesium is implanted into the sample surface leading to more negative ion formation

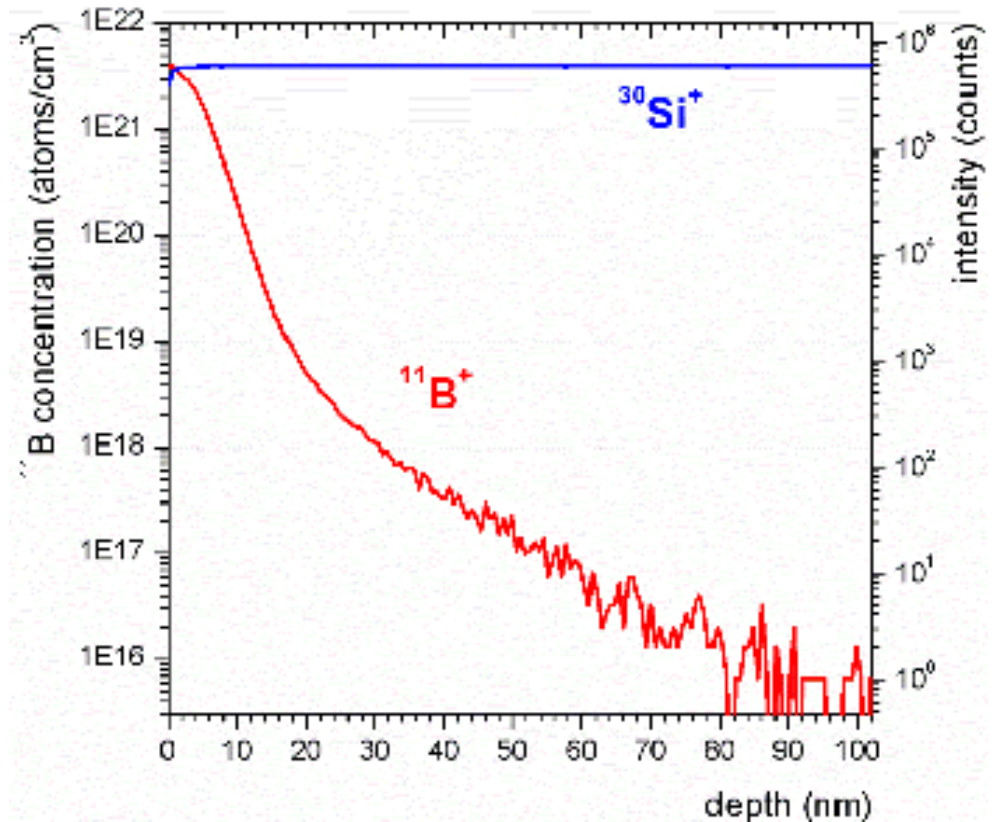
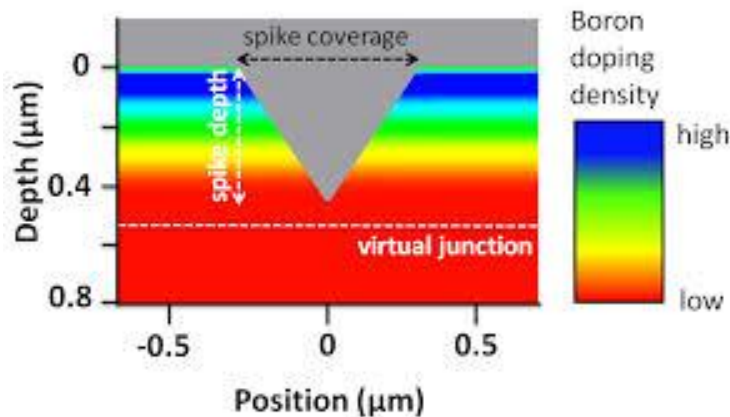
Surface Imaging

By rastering a fine focussed ion beam over the surface, a chemical map of the surface can be obtained simultaneously.



Depth Profiling

Depth profiling is achieved through the use of two beams: one beam is used to etch the surface (C_{60}^{n+}) and the second beam (LMIG) continually analyses the crater.



Depth profile of shallow B implant into Si wafer with 6 orders of dynamic range with detection limit below $1\text{E}16$ at/cc

3D Analysis

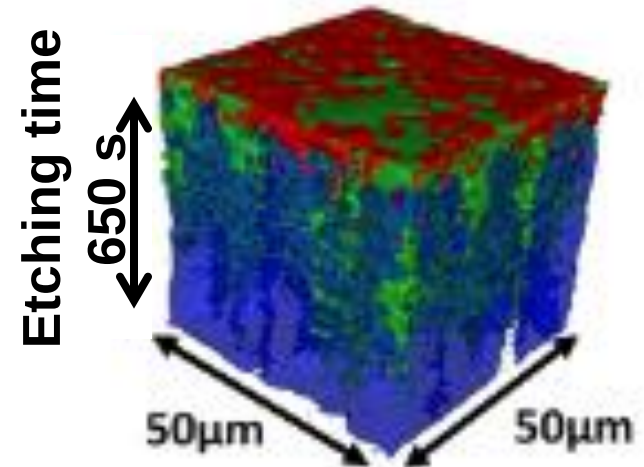
Through the combination of the spectral information, depth analysis and imaging, 3D visualization of the sample is possible.



■ Mn⁺



■ Li₃F₂⁺

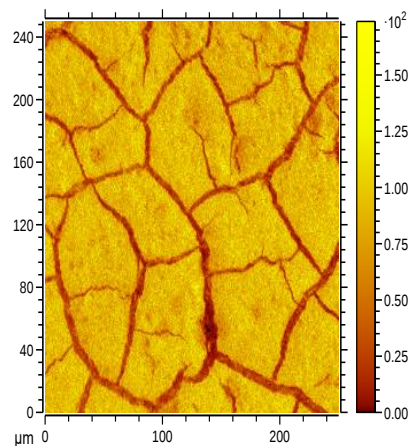


■ Ti⁺

Papa Francis' Sample Analysis

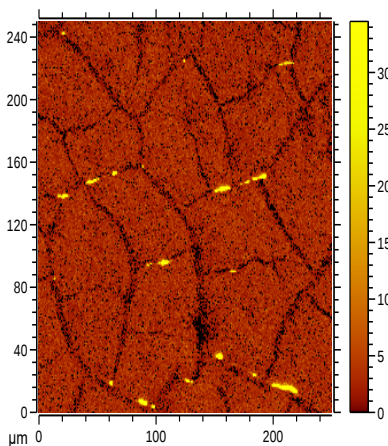
- Characterize the anode surface before and after dye adsorption in order to determine the characteristic distributions of the different compounds and the quality of the anode.
- Ion density maps or secondary ion images were acquired in both positive and negative ion mode.
- The secondary ion images represent “chemical images” showing characteristic distributions of the elements/compounds.

TOFSIMS positive ion mode images of anode before dye adsorption (ITO + semiconductor)



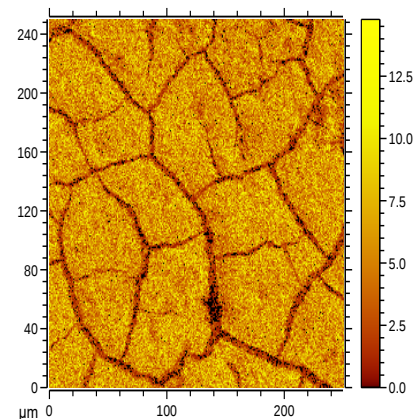
47.95 u
MC: 174; TC: 5.148e+006

❖ m/z 47.95, titanium



115.04 u
MC: 35; TC: 2.195e+005

❖ m/z 115.04, indium

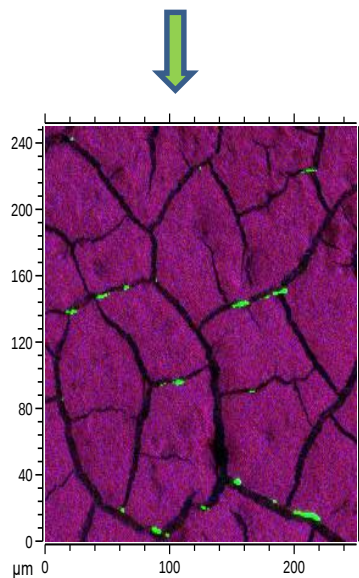


91.05 u
MC: 15; TC: 3.597e+005

❖ m/z 91.05, Benzene ring, fragment from rGONS

Data confirms that:

❖ rGONS and TiO_2 are homogenously mixed and appear where we expected.



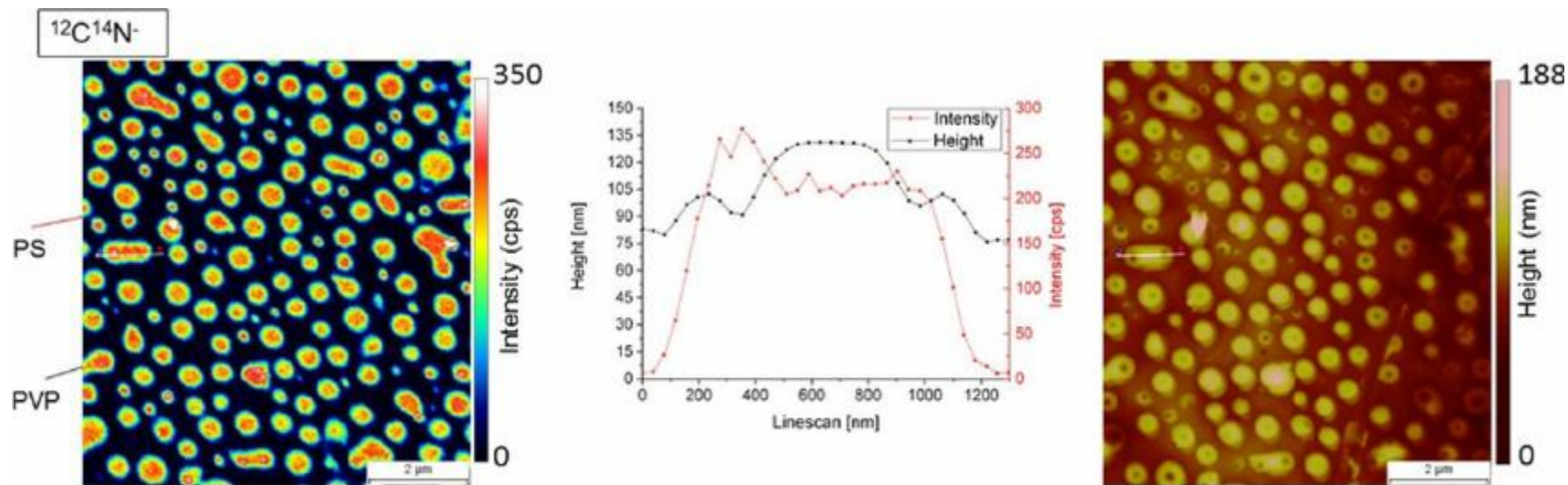
Overlay of 47.95 u, 115.04 u, 91.05 u

RGB plot

Applications

Analyte Types

- **Paints and coatings**
- **Pharmaceuticals**
- **Forensics**
- **Biomaterials and polymers**



SIMS

AFM

